

**AMENDMENTS TO THE CLAIMS**

1-12. (Canceled)

13. (Currently Amended) A method of cleaning a substrate of a liquid crystal display panel comprising:

moving the substrate continuously in a linear direction;  
jetting deionized water that carries ultrasonic waves onto a side surface of the substrate;  
brushing the side surface of the substrate with a brush that extends partially along the side surface of the substrate; and  
cleaning upper and lower surfaces of the substrate.

14. (Previously Presented) The method of claim 13, wherein the brush is rotatable.

15. (Canceled)

16. (Previously Presented) The method of claim 13, wherein cleaning the upper and lower surfaces of the substrate comprises:

rotating cleaning brushes on the upper and lower surface of substrate.

17. (Canceled)

18. (Previously Presented) The method of claim 16, wherein the cleaning brushes are arranged at the upper and lower surfaces of the substrate, respectively.

19-22. (Canceled)

23. (Currently Amended) A method of cleaning a substrate of a liquid crystal display panel comprising:

removing foreign substances on a side surface of the substrate by jetting deionized water that carries ultrasonic waves onto the side surface of the substrate with a water jet device and brushing the side surface of the substrate with cleaning brushes that extend partially along the side surface of the substrate while moving the substrate continuously in a linear direction; and

removing foreign substances on the upper and lower surfaces of the substrate by brushing the upper and lowers surface of the substrate with brushes.

24. (Original) The method of claim 22, wherein the water jet device causes vibration on the side surface of the substrate.

25. (Original) The method of claim 23, wherein the vibration is generated by ultrasonic waves.

26-27. (Canceled)

28. (Currently Amended) A method of cleaning a substrate having an upper surface and a lower surface separated by at least two opposing side surfaces, the method comprising:

moving the substrate continuously in a linear direction

brushing at least two opposing side surfaces with cleaning brushes that extend partially along the at least two opposing side surfaces of the substrate;

cleaning at least one of the upper and lower surfaces; and

spraying water that carries ultrasonic waves onto the at least two brushed side surfaces.

29. (Previously Presented) The method of claim 28, further including brushing at least two opposing side surfaces before brushing at least one of the upper and lower surfaces.

30. (Previously Presented) The method of claim 28, wherein the water includes deionized water.

31. (Canceled)

32. (Previously Presented) The method of claim 28, wherein cleaning at least one of the upper and lower surfaces includes brushing the at least one of the upper and lower surfaces.